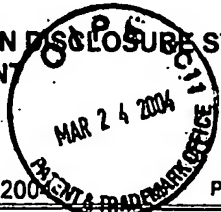


Atty. Dkt. No.	M#	Client Ref.
	0302644	P-1698.000-US

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**



Applicant: FLAGELLO et al.	
Appn. No.: 10/698,012	
Filing Date: October 31, 2003	
Examiner: Unassigned	Group Art Unit: 2854

Date: March 24, 2004 Page 1 of 4

**U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PR	AR 2004/0000627	01/2004	Schuster	250	201.2	
↑	BR 6,600,547 B2	07/2003	Watson et al.	355	30	
	CR 2002/0163629 A1	11/2002	Switkes et al.	355	53	
	DR 2004/0021844 A1	02/2004	Suenaga	355	67	
	ER 3,573,975	04/1971	Dhaka et al.	117	212	
	FR 3,648,587	03/1972	Stevens	95	44 R	
	GR 4,346,164	08/1982	Tabarelli et al.	430	311	
	HR 4,396,705	08/1983	Akeyama et al.	430	326	
	IR 4,480,910	11/1984	Takanashi et al.	355	30	
	JR 4,509,852	04/1985	Tabarelli et al.	355	30	
	KR 5,040,020	08/1991	Rauschenbach et al.	355	53	
	LR 5,121,256	06/1992	Corle et al.	359	664	
↓	MR 5,610,683	03/1997	Takahashi	355	53	
PR	NR 5,715,039	02/1998	Fukuda et al.	355	53	

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					Enclosed	No	Enclose	No
PR	OR WO 2004/019128 A2	03/2004	WIPO	Omura et al.	X			
↑	PR JP 58-202448	11/1983	Japan	Yoshio et al.	X			
	QR WO99/49504	09/1999	WIPO	Fukami et al.	X		X	
	RR WO 03/077036 A1	09/2003	WIPO	Schuster	X			
	SR EP 0023231 B1	02/1981	Europe	Tabarelli et al.	X			
	TR EP 0418427 A2	03/1991	Europe	Miyake	X			
	UR EP 1039511 A1	09/2000	Europe	Hirukawa et al.	X			
↓	VR DD 224448 A1	07/1985	E. Germany	Hesse et al.		X		
	WR DD 242880 A1	02/1987	E. Germany	Kuch et al.		X		
PR	XR FR 2 474 708	07/1981	France	Letellier		X		

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PR	YR	S. Owa et al., "Potential performance and feasibility of immersion lithography," NGL Workshop 2003, July 10, 2003	X		
PR	ZR	H. Hogan, "New Semiconductor Lithography Makes a Splash," Photonics Technology World, October 2003, pp.1-3	X		
PR	AAR	M. Switkes et al., "Immersion Lithography at 157 nm," MIT Lincoln Lab, Orlando 2001, 1, December 11, 2001	X		

Examiner: *[Signature]* Date Considered: 11-30-04

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office					Atty. Dkt. No.	M#	Client Ref.	
					0302644		P-1698.000-US	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>					Applicant: FLAGELLO et al.			
					Appln. No.: 10/698,012			
					Filing Date: October 31, 2003			
					Examiner: Unassigned      Group Art Unit: 2854			
Date: March 24, 2004.      Page <u>2</u> of <u>4</u>								
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	CCR 5,900,354	05/1999	Batchelder	430	395			
	DDR 6,191,429 B1	02/2001	Suwa	250	548			
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	FFR 6,603,130 B1	08/2003	Bisschops et al.	250	492.1			
	GGR 6,633,365 B2	10/2003	Suenaga	355	53			
	HHR 2003/0123040 A1	07/2003	Almog	355	69			
	IIR 2003/0174408 A1	09/2003	Rostalski et al.	359	642			
	JJR							
	KKR							
LLR								
MMR								
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					Enclosed	No	Enclose	No
	NNR JP 62-65326	03/1987	Japan	Noboru	X			
	OOR JP 62-121417	06/1987	Japan	Koji	X			
	PPR JP 63-157419	06/1988	Japan	Mamoru	X			
	QQR JP 4-305915	10/1992	Japan	Hisao et al.	X			
	RRR JP 4-305917	10/1992	Japan	Hisao et al.	X			
	SSR JP 6-124873	05/1994	Japan	Kazuo	X		X	
	TTR JP 7-220990	08/1995	Japan	Hiroshi et al.	X			
	UUR JP 10-228661	08/1998	Japan	Kotaro	X			
	VVR JP 10-255319	09/1998	Japan	Masashi et al.	X			
	WWJ JP 10-303114	11/1998	Japan	Kyoichi	X		X	
OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)								
XXR	M. Switkes et al., "Immersion Lithography at 157 nm," J. Vac. Sci. Technol. B., Vol. 19, No. 6, Nov./Dec. 2001, pp. 2353-56				X			
YYR	M. Switkes et al., "Immersion Lithography: Optics for the 50 nm Node," 157 Anvers-1, Sept. 4, 2002				X			
ZZR	B. J. Lin, "Drivers, Prospects, and Challenges for Immersion Lithography," tsmc, Inc., Sept. 2002				X			
Examiner:					Date Considered: 11-70-04			
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.								

FORM PTO-1449 (modified)  
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(PW FORM PAT-1449)  
Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	0302644	P-1698.000-US

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: FLAGELLO et al.

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Filing Date: October 31, 2003

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Date: March 24, 2004

Page 3 of 4

Examiner: Unassigned

Group Art Unit: 2854

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AAA					
	BBB					
	CCC					
	DDD					
	EEE					
	FFF					
	GGG					
	HHH					
	III					
	JJJ					
	KKK					
	LLL					
	MMN					
	NNN					

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					Enclosed	No	Enclose	No
PT	OOO JP 10-340846	12/1998	Japan	Taketo	X		X	
PT	PPP JP 2001-91849	04/2001	Japan	Shinichiro et al.	X			
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	RRR							
	SSS							
	TTT							
	UUU							
	VVV							
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PT	XXX	B.J. Lin, "Proximity Printing Through Liquid," IBM Technical Disclosure Bulletin, Vol. 20, No. 11B, April 1978, p. 4997	X		
PT	YYY	B.J. Lin, "The Paths To Subhalf-Micrometer Optical Lithography," SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269	X		
PT	ZZZ	G.W.W. Stevens, "Reduction of Waste Resulting from Mask Defects," Solid State Technology, August 1978, Vol. 21 008, pp. 68-72	X		
PT	AAA	T. Matsuyama et al., "Nikon Projection Lens Update," Nikon Corporation, (date unknown)	X		

Examiner

Date Considered: 11-30-04

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)  
To: U.S. Department of Commerce  
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0302644

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**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: FLAGELLO et al.

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Examiner: Unassigned

Group Art Unit 2854

**U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	BBB					
	CCC					
	DDD					
	EEE					
	FFF					
	GGG					
	HHH					

**FOREIGN PATENT DOCUMENTS**

FOREIGN PATENT DOCUMENTS						English Abstract		Translation Readily Available		
		Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No	Enclose	No
		IIIR								
		JJJJ								
		KKK								
		LLLL								
		MMN								
		NNN								
		OOO								
		PPP								

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

Q	QQQ	S. Owa et al., "Immersion lithography; its potential performance and issues," SPIE Microlithography, 5040-186, Feb. 27, 2003	X			
R	RRR	Nikon Precision Europe GmbH, "Investor Relations - Nikon's Real Solutions", May 15, 2003	X			
S	SSS	H. Kawata et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity," Microelectronic Engineering 9 (1989), pp. 31-36	X			
T	TTT	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography," J. Vac. Sci. Technol. B, Vol. 17(6), Nov/Dec 1999	X			
U	UUU	B.W. Smith et al., "Immersion Optical Lithography at 193nm, FUTURE FAB International, Issue 15, July 11, 2003	X			
V	VVV	H. Kawata et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens," Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177	X			
W	WWW	G. Owen et al., "1/8µm Optical Lithography," J. Vac. Sci. Technol. B, Vol. 10, No. 6, Nov/Dec. 1992, pp. 3032-3036	X			
X	XXX	Owa et al., "Advantage and feasibility of immersion lithography", Nikon Corporation, (date unknown)				

Examiner

Date Considered:

11-30-04

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

Attorney Docket: 081468-0302644  
Client Reference: P-1698.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION  
FLAGELLO ET AL.

Confirmation Number: 7154

Application No.: 10/698,012

Group Art Unit: 2854

Filed: October 31, 2003

Examiner: Unassigned

Title: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
P2	Joeri LOF et al.	10/705,783	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P4	Helmar VAN SANTEN et al.	10/743,271	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P4	Johannes C.H. MULKENS et al.	10/743,266	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P2	Klaus SIMON et al.	10/724,402	12/01/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P2	Joannes T. DESMIT et al.	10/705,804	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P2	Antonius T.A.M. DERKSEN et al.	10/705,785	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P2	Arno J. BLEEKER	10/715,116	11/18/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P2	Bob STREEFKERK et al.	10/719,683	11/24/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P2	Joeri LOF et al.	10/705,816	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
P2	Joeri LOF et al.	10/705,805	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card

\*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.